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Xerox Docket No. D/A1203

PATENT APPLICATION

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THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Pinyen LIN et al.

Application No.: 09/683,547

Filed: December 26, 2001

Docket No.: 109128

For: SPACER LAYER FOR ELECTROPHORETIC DISPLAY DEVICE

PRELIMINARY AMENDMENT

**RECEIVED**

Director of the U.S. Patent and Trademark Office  
Washington, D. C. 20231

**FEB 21 2002**

Technology Center 2600

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Please replace paragraph [0054]<sup>3</sup> as follows:

*a1*  
[0054]<sup>3</sup> The etched photoresist spacer layer may be formed by first laminating the photoresist layer onto a conductive metal layer surface, i.e., the conductive metal layer of the bottom substrate, and masked. After exposure to, for example, ultraviolet light to chemically alter the photoresist at exposed portions, the mask is removed and the photoresist is etched accordingly.

Please replace paragraph [0059]<sup>5</sup> as follows:

*a2*  
[0059] Once laminated, a mask 196 is placed upon a surface of one of the photoresist layers 192 as shown in Figure 11, the mask having a pattern such that it covers the area where etching is not desired. The structure is then exposed to, for example, ultraviolet light that chemically alters the exposed portions of the photoresist films. The exposed, developed